

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Huilong Zhu, et al.

**Examiner:** Chuong A. Luu

**Serial No:** 10/709,239

**Art Unit:** 2818

**Filed:** April 23, 2004

**Docket:** FIS920030375US1 (17192)

**For:** STRUCTURES AND METHODS FOR  
MANUFACTURING OF DISLOCATION  
FREE STRESSED CHANNELS IN BULK  
SILICON AND SOI CMOS DEVICES BY  
GATE STRESS ENGINEERING WITH  
SiGe AND/OR Si:C

**Dated:** August 27, 2007

**Confirmation No:** 3238

Mail Stop AF  
Commissioner for Patents  
United States Patent Office  
Alexandria, VA 23313-1450

**RESPONSE UNDER 37 C.F.R. § 1.116**

Sir:

In response to the Final Rejection dated June 26, 2007, Applicants submit the following remarks for entry of record in the above-identified patent application.

**Amendments to the Claims** are provided in the **Listing of Claims** beginning on page 2 of this paper.

**Remarks** begin on page 9 of this paper.

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**CERTIFICATE OF ELECTRONIC FILING**

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Dated: August 27, 2007

  
Steven Fischman